

<b>Notice of References Cited</b>	Application/Control No. 10/683,727	Applicant(s)/Patent Under Reexamination SHERMAN, ARTHUR	
	Examiner Kelly Stouffer	Art Unit 1762	Page 1 of 1

**U.S. PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
*	A	US-4,949,671	08-1990	Davis et al.	118/725
*	B	US-4,882,008	11-1989	Garza et al.	216/48
	C	US-			
	D	US-			
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	F	US-			
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	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

**FOREIGN PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N					
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	S					
	T					

**NON-PATENT DOCUMENTS**

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Dillon, AC et al. "Surface chemistry of Al <sub>2</sub> O <sub>3</sub> deposition using Al (CH <sub>3</sub> ) <sub>3</sub> and H <sub>2</sub> O in a binary reaction sequence" Surf. Sci. 322 (Jan 1995) 230-242.
	V	
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\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)  
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.